Solution-processable and Photo-programmable Logic Gate Realized by Organic Non-

volatile Floating-gate Photomemory

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Table S1. The absorbance of  $N_3$  stretching and the corresponding nitrene-forming

Exposure	N2200 and blend f	d azide ĭlm	DPP-DTT blend	and azide film	BCP and azide blend film	
time (min)	Absorbance of N <sub>3</sub> stretching	Efficiency <sup>a</sup> (%)	Absorbance of N <sub>3</sub> stretching	Efficiency <sup>a</sup> (%)	Absorbance of N <sub>3</sub> stretching	Efficiency <sup>a</sup> (%)
Baseline	0.00756	N/A	0.37472	N/A	0.00119	N/A
0	0.01282	0.00	0.37957	0.00	0.15704	0.00
10	0.01180	19.39	0.37853	21.44	N/A	N/A
20	0.01034	47.15	0.37580	77.73	N/A	N/A
30	0.01006	52.47	0.37536	86.80	0.07948	49.77

<sup>*a*</sup> Given that the formation of nitrene is the photolysis of  $N_3$ , the nitrene-forming efficiency can be traced by the variation of absorbance of  $N_3$  in FTIR under UV light exposure. Based on the absorbance of  $N_3$  stretching signal in the FTIR spectra of N2200 and azide blend film, DPP-DTT and azide blend film and BCP and azide blend film, the nitrene-forming efficiency can be calculated using the following formula:

$$\text{Efficiency} = \left\{ 1 - \frac{(A_X - A_{baseline})}{(A_0 - A_{baseline})} \right\} \times 100\%$$
(S1)

Where  $A_X$  is the absorbance of N<sub>3</sub> stretching at exposure time of x min,  $A_0$  is the initial absorbance of N<sub>3</sub> stretching and  $A_{\text{baseline}}$  stands for the absorbance of baseline.

**Table S2.** AFM images and height profiles of photopatterned BCP films with different BCP to azide weight ratios. <sup>*a*</sup> Film retention was calculated by thickness of developed film/thickness of as-spun film\*100%.

BCP:azide	As-spi	ın film	Develo	Film		
weight ratio	Height image	1D profile	Height image	1D profile	retention <sup>a</sup>	
1:1	Rq=1.5 nm Rq=1.5 nm 1. Height Sensor 20.9 m 0.0 m 100 cm	40 50 50 50 50 50 50 50 50 50 5	Rq=1.43 nm Rq=1.43 nm 0.0 1: Height Sensor 20.0 µm 0.0 nm 100 nm 100 nm	40 After development 50 52 52 52 52 52 52 52 52 52 52	100%	
1:2	Rq=2.06 nm Rg=2.06 nm 1 Helight Sensor 20.0 µm 20 m 100 nm	4 - A-deposited film	Rq=2.98 nm Rq=2.98 nm 1 Height Sensor 200 µm 0.0 m 15 Height Sensor 200 µm	40 After development 10 10 10 10 10 10 10 10 10 10	100%	
1:4	Rq=1.35 nm Rq=1.35 nm 100 m 100.0 m	40 43 45 45 45 45 45 45 45 45 45 45	Rq=0.91 nm Rq=0.91 nm 1: Height Sensor 20.0 µm 8.0 m 100.0 am	40 	100%	

Sample	A <sub>1</sub>	$ au_1$ (ns)	$A_2$	$ au_2$ (ns)	$ au_{ m average}$ (ns)	CTE (%)
$S_1 \rightarrow S_0$						
BCP/ZnTPP	288.79	0.49	35.93	2.68	0.74	77
BCP/ZnTPP/N2200	90474.1	0.17	144.6	0.91	0.17	
$S_2 \rightarrow S_0$						
BCP/ZnTPP	74.44	0.01	8903.5	0.45	0.45	67
BCP/ZnTPP/N2200	1.19	0.15	147	0.80	0.15	07

 Table S3. TRPL fitting results of BCP/ZnTPP and BCP/ZnTPP/N2200 under the excitation wavelength of 372 nm.

Charge- trapping material/ Charge- transporting material	Light wavelength (nm)	Lowest Photo- programming time (s)	Light intensity (mW cm <sup>-2</sup> )	On/Off current ratio	Memory window (V)	Photoresponsivity (AW <sup>-1</sup> )	The deposited method for charge- transporting material	Reference
PVSK / BPE- PTCDI	530	60	10	10 <sup>3</sup>	14	0.002	Thermal evaporation	ACS Appl. Mater. Interfaces 2021, 13, 20417–20426
SoI-PDI/ BPE-PDI	405	20	10	105	7.8	0.2	Thermal evaporation	<i>Adv. Mater.</i> 2020, 32, 2002638
C <sub>70</sub> /C <sub>60</sub>	white LED	50 ms & V <sub>g</sub> = 22 V	3.76	N/A	2.5	N/A	Thermal evaporation	<i>Sci. Rep.</i> 2016, 6, 30536
PVA/C <sub>60</sub>	405 nm	60	0.13	N/A	69.3	N/A	Thermal evaporation	Phys.         Chem.           Chem.         Phys.,           2016,         18,           1310813117
PVAn/QD/ PEPTC	450	10	14	10 <sup>4</sup>	14	0.0143	Thermal evaporation	ACS Appl. Mater. Interfaces 2023, 15, 1, 1675– 1684
PDVT-10/ N2200	white	1	5	105	10	5	Spin coating	ACS Photonics 2021, 8, 10, 3094– 3103
PPylr/C8- NDI	455	30	N/A	10 <sup>3</sup>	15	N/A	Thermal evaporation	ACS Photonics 2023, 10, 12, 4509– 4518
TIPS-4/C8- PDI	530	10	5	10 <sup>4</sup>	N/A	0.004	Thermal evaporation	Adv. Funct. Mater. 2024, 2416306
ZnTPP/ N2200	405	0.1	59.73	105	18	0.00125	Spin coating	This work

**Table S4** The organic photomemories with *n*-type charge-transporting materials and the corresponding electrical performance.

Semiconductor	Device type	Classification tasks	Accuracy	Reference
Pentacene	Organic field- effect transistor	Handwritten digits	63.21%	<i>Small</i> <b>2021</b> , <i>17</i> , 2103837.
(Poly[2,5-bis(2- octyldodecyl)pyrrolo[3,4- c]pyrrole-1,4(2H,5H)-dione- 3,6-diyl)-alt-(2,2';5',2";5",2"'- quaterthiophen-5,5'''- diyl)](PDPP4T)/chhlorophyll- a	Organic field- effect transistor	Handwritten digits	79%	<i>Npj Flex.</i> <i>Electron.</i> <b>2022</b> , <i>6</i> , 30.
2-hexylthieno[4,5-b][1] benzothieno[3,2-b][1] benzothiophene (BTBTT6- syn)	Organic field- effect transistor	Handwritten digits	90%	<i>Nat. Commun.</i> <b>2023</b> , <i>14</i> , 2281.
Poly(3-hexylthiophene-2,5- diyl)(P3HT)/[6,6]-phenyl- C61-butyric acid methyl ester(PCBM)	Organic ion- gated transistor	Fashion products	89.5%	<i>Nat. Photonics</i> <b>2023</b> , <i>17</i> , 629.
Poly[2,5-(2-octyldodecyl)-3,6- diketopyrrolopyrrole-alt-5,5- (2,5-di(thien-2-yl)thieno [3,2- b]thiophene)](DPPDTT) /Matrimid 5218(MI)	Organic field- effect transistor	Handwritten digits	50~80%	<i>Adv. Mater.</i> <b>2023</b> , 2310155.
2-(4,5-bis(4-fluorophenyl)-1- phenyl-1H-imidazol-2-yl)-4- (di(naphthalen-2- yl)amino)phenol(DNH-F)	Memristor	RGB color images	90%	<i>Nat. Commun.</i> <b>2023</b> , <i>14</i> , 5775.
Pentacene	Organic field- effect transistor	Handwritten digits	94.8%	<i>ACS</i> <i>Nano</i> <b>2023</b> , 17, 24, 25552.
DPPDTT	Organic ion- gated transistor	Handwritten digits	97.21%	<i>Adv. Mater.</i> <b>2024</b> , 36, 2312473.
2,7-dioctyl[1]benzothieno[3,2- b][1]benzothiphen (C8-BTBT)	Organic field- effect transistor	Handwritten digits	93.9%	<i>Chem. Eng. J.</i> <b>2024</b> , 498, 155237
N2200/ZnTPP	Organic non- volatile photomemory	Handwritten digits	94.66%	This work

 Table S5. The state-of-the-art organic transistor-based neuromorphic devices.



Figure S1. Schematic description of the fabrication processes for photopatterned and photo-programmable logic gate through photopatterning using azide as photo-crosslinker.

(a)



## (b)







(d)







-- 1.10



**Figure S3.** (a)FTIR spectra of BCP, ZnTPP and BCP/ZnTPP film to confirm the chelating effect between BCP and ZnTPP. (b) The absorption spectra of ZnTPP and BCP/ZnTPP film.



Figure S4. Photo-patterned DPP-DTT film with millimeter-scale dimension.



**Figure S5.** Stability test of conjugated polymer under UV light exposure. Transfer curves of (a)pure N2200 derived FET and (b) pure DPP-DTT derived FET.



**Figure S6.** Transfer curves of photo-patterned *n*-type OFETs with N2200 to azide ratio ranged from (a)1:0.01, (b)1:0.02, (c)1:0.04, (d)1:0.1 to (e)1:0.2. Transfer curves of photo-patterned *p*-type OFET with DPP-DTT to azide ratio ranged from (f)1:0.01, (g)1:0.02, (h)1:0.04, (i)1:0.1 to (j)1:0.2. The transfer characteristics of the *n*-type OFETs were recorded by sweeping the gate voltage ( $V_{GS}$ ) between -20 and 100 V under a fixed drain voltage ( $V_{DS}$ ) of 100 while the transfer characteristics of the *p*-type OFETs were recorded by sweeping the gate voltage ( $V_{GS}$ ) between 20 and -100 V under a fixed drain voltage ( $V_{DS}$ ) of -100 V.



**Figure S7** FTIR spectra of homopolymer and azide blend films before and after UV light exposure: (a) PS and azide blend film with enlarged region ranged from (b) 2200 cm<sup>-1</sup> to 2000 cm<sup>-1</sup> and (c) 3300 cm<sup>-1</sup> to 2600 cm<sup>-1</sup>; (d) PMAA and azide blend film with enlarged region ranged from (e) 2200 cm<sup>-1</sup> to 2000 cm<sup>-1</sup> and (f) 3300 cm<sup>-1</sup> to 2600 cm<sup>-1</sup>.



**Figure S8.** Absorption spectra of photo-crosslinked BCP/ZnTPP before and after development.



**Figure S9.** (a) The memory window of BCP/ZnTPP/N2200 based photomemory under different light sources. (b) The temporal  $I_{\rm DS}$  under different  $V_{\rm DS}$  ranged from 0.5 V to 10 V (405 nm, 60 mWcm<sup>-2</sup>). (c) Transfer characteristics at  $V_{\rm DS}$ =100 V of the BCP/N2200 OFET at initial state, under 405 nm light illumination (60 mWcm<sup>-2</sup>) for 120 s and erasing at  $V_{\rm GS}$ =60 s for 0.5 s. (d) The photo-responsive current toward time for the BCP/N2200 OFET under 405 nm illumination (120 s, 60 mW cm<sup>-2</sup>) at  $V_{\rm DS}$ =100 V.



Figure S10. The proposed mechanism of photo-recordable behavior by lower photon energy.



**Figure S11.** Four cycles of repeated LTP and LTD response by optical and electric pulse trains and the corresponding accuracy. (a) first cycle, (b)second cycle, (c) third cycle and (d) fourth cycle.



**Figure S12.** Switching characteristics of the photo-programmable inverter under 830 nm and 650 nm light stimuli.



**Figure S13.** Time traces of the input and output voltage for inverter consisting of DPP-DTT based OFET and BCP/N2200 based OFET under 405 nm light illumination.